



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Group Art Unit: 2851
Examiner: Hung Nguyen
Confirmation No.: 6971

DPW

In Re PATENT APPLICATION Of:

Applicants: Ryoichi AOYAMA et al.)
Serial No.: 10/748,240)
Filed: December 31, 2003) **AMENDMENT AFTER**
For: SELF-CLEANING METHOD FOR) **ALLOWANCE**
SEMICONDUCTOR EXPOSURE)
APPARATUS)
Allowed: August 5, 2005)
Docket No.: OKI 395)

September 30, 2005

MAIL STOP ISSUE FEE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR § 1.312, please amend the above-identified application as follows: